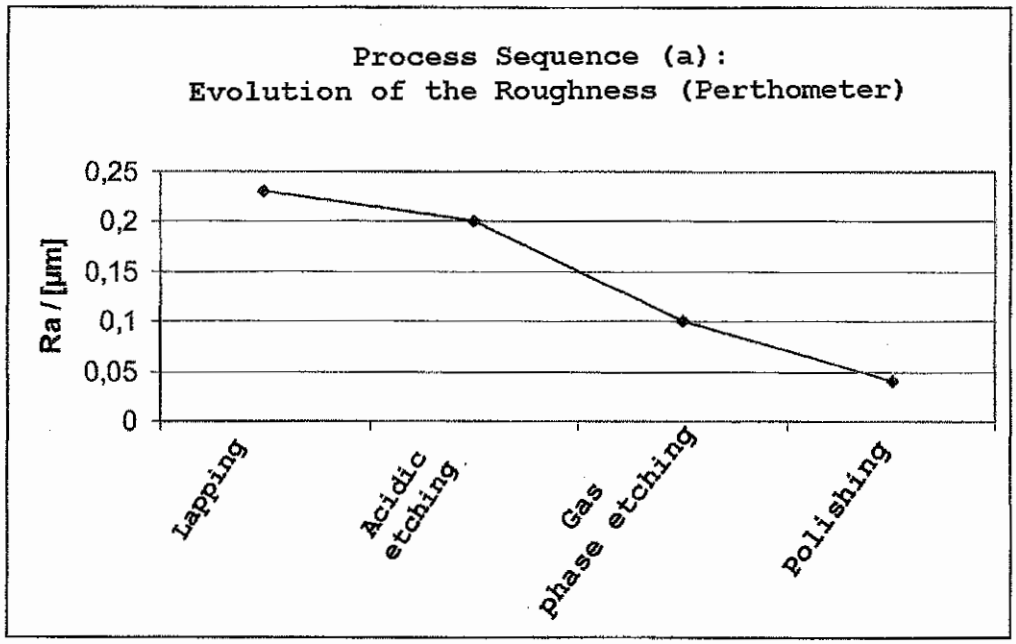

Process Sequence (a):
Evolution of the Roughness (Perthometer)
Ra / [µm]
0,25
0,2
0,15
0,1
0,05
0
Lapping
Acidic etching
Gas phase etching
Polishing

Fig. 1

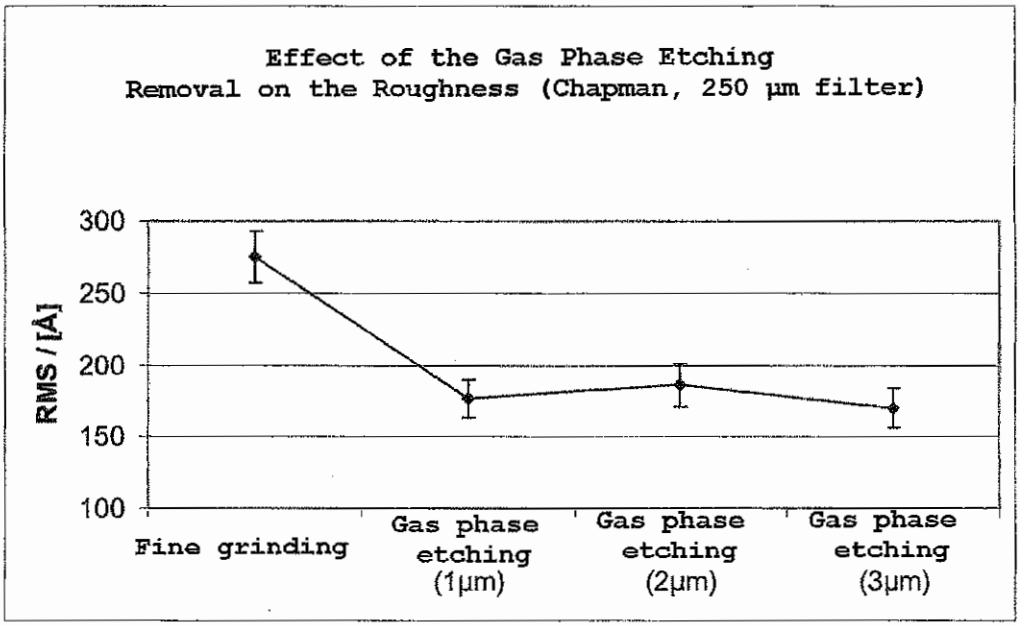

Effect of the Gas Phase Etching
Removal on the Roughness (Chapman, 250 µm filter)
RMS / [Å]
300
250
200
150
100
Fine grinding
Gas phase etching (1µm)
Gas phase etching (2µm)
Gas phase etching (3µm)

Fig. 2